

[ABSTRACT]

Disclosed is a polishing pad including a polishing layer having a circular polishing surface, wherein the polishing pad is provided with a spiral groove or concentric grooves including a plurality of annular grooves arranged concentrically, the spiral groove and the concentric grooves being disposed spanning from a central region to a peripheral edge region of the polishing surface, and radial grooves including line segment-shaped grooves extending from the central region toward the peripheral edge region. The line segment-shaped grooves have a first end portion in a radial groove at a distance of 5 to 10% of the radius of the polishing surface from a center of the radial grooves, and a second end portion in a region at a distance of 35 to 70% of the radius of the polishing surface from the center of the radial grooves, and the line segment-shaped grooves have an average length of 30 to 65% of the radius of the polishing surface. A cross-sectional area S_a (mm^2) of the line segment-shaped grooves and a cross-sectional area S_b (mm^2) of the spiral groove or the concentric grooves satisfy $0.1 \leq S_b/S_a < 1.0$.